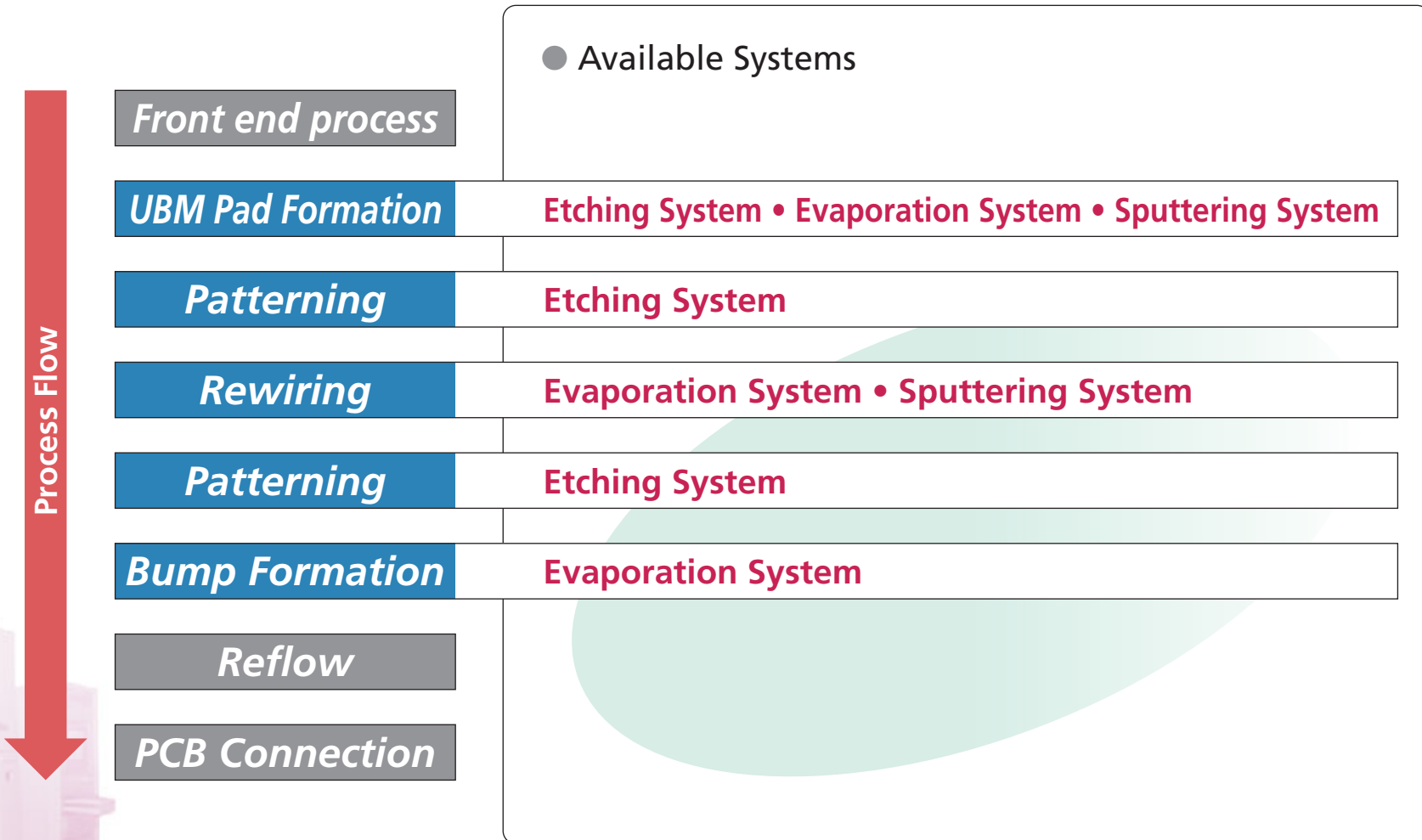


High Density Packaging Technology / Manufacturing Process



Sputtering System for CSP

SRH-820



ULVAC, Inc.

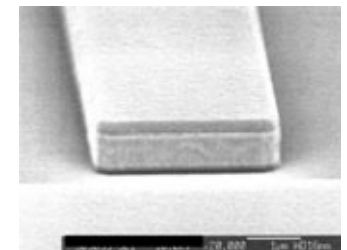
- Available for max. 8 inch substrate
Available for small-size substrate by the change of substrate holders.
- Available for max. 7 processes
Be able to select max. 7 positions for heating, etching, sputtering treatment chamber.
- Available for high-throughput process
Be able to treat single substrate at the shortest time - 35 sec.

Dry Etching System for UBM

APIOS NE-7800



ULVAC, Inc.



Metal/Au/Metal

- Available for lump etching of UBM (Ti, Cr, Au, Cu, TiW, Ni) High Density Plasma Etching System
- Best modification for sputter-like metal etching and post-treatment (residuals-free)
- Excellent repeatability and stability
- Available for multi-chamber (3 chamber)
- High cost performance